

# Optical and Electrical Properties of Cu-Based Thin Films by Aerosol Assisted Chemical Vapor Deposition

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Cu-based thin films with doping of Zn and Al were synthesized by aerosol-assisted chemical vapor deposition (AACVD). The AACVD allows simple fabrication method which produced homogenous film when deposited on glass substrates. The structural, optical transmittance and electrical properties of Cu-based thin film with Zn and Al doping were obtained by X-ray diffraction (XRD), UV-Vis spectroscopy and 4-point probe, respectively. XRD results showed peaks for ZnO and CuAlO<sub>2</sub> indicating that binary Cu thin film with Zn and Al doping was successfully synthesized by AACVD. The optical band gap of 3.6 and 4.11 eV was obtained for single Cu<sub>2</sub>O and ZnO thin film, respectively. The best electrical performance was achieved by single Cu<sub>2</sub>O thin film with  $R_s = 102.8 \Omega/\text{sq}$ , however, it was obtained at low  $T$  of 28%. The doping of Zn and Al to Cu-based thin film did not improve their electrical and optical properties.

**Keywords:** AACVD, copper oxide thin films, CuAlO<sub>2</sub>, transparent conducting film

## I. INTRODUCTION

Copper oxide forms two types of oxide: copper (I) oxide (CuO, *tenorite*) and copper (II) oxide (Cu<sub>2</sub>O, *cuprite*) which both exhibits *p*-type characteristics of semiconductor with band gap of 2.1 and 1.2 eV, respectively. Conduction of *p*-type semiconductor is attributed to the presence of holes in the valence band due to doping or annealing. Copper oxide shows good electrical and optical properties which is suitable for wide range of applications such as photovoltaic material (Kaur et al., 2017), gas sensor (Navale et al., 2017) and catalytic application (Ren et al., 2015). Copper oxide also has the advantages of low cost, non-toxic and high availability (1000

times abundant than silver).

Previously, copper oxide thin film was deposited on different substrates by various methods such as pulsed magnetron sputtering (Alkoy & Kelly 2005), DC magnetron sputtering (Mugwang'a et al., 2013), thermal evaporation (Navale et al., 2017) and spin coating (Johan et al., 2011). On the other hand, Cu-based nanostructure such as copper nanowires and nanofibers can be obtained by solution-processed (Duong & Kim 2017) and electrospinning (Wu et al., 2010), respectively. Deposition method is important in determining the properties of the materials, thus, we demonstrate the fabrication of Cu-based thin film and metal doping by aerosol-assisted

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chemical vapor deposition (AACVD).

AACVD is a low cost, high deposition rate and facile method, which is uniform and good quality thin film can be obtained (Bakar et al., 2013). There are a few works reported on the Cu-based thin film using AACVD. Previous study has utilized the tube furnace variant of AACVD to synthesize molecular metal organics (MMO) precursors of copper and cobalt mixed metal oxide using heterobimetallic complex consist of *N,N*-dimethylaminoethanol (DMAE), trifluoroacetate (TFA) and tetrahydrofuran (THF) (Hamid et al., 2008). Copper oxide thin films deposited onto glass substrates by AACVD for antimicrobial activity was reported by Hassan et al (2014). Copper oxide and copper gallium oxide was prepared by AACVD using different metal precursor ( $\text{Cu}(\text{acac})_2$  and  $\text{Cu}(\text{thd})_2$ ) and solvents (toluene, dichloromethane, THF) (Knapp et al., 2014). However, these studies were not reporting the electrical and optical properties of Cu-based using AACVD method. So far in literature there was no attempt to deposit single CuO and binary metal oxide of  $\text{Al}_2\text{O}_3$  and ZnO as a thin film on borosilicate glass substrates using AACVD setup. So far, binary of  $\text{CuAlO}_2$  also exhibits *p*-type characteristics was previously synthesized by solution-processed (Chiu & Huang 2012; Tonooka et al., 2002), spray pyrolysis (Singh et al., 2008) and DC sputtering (Banerjee et al., 2003) whereas Zn-doped CuO was synthesized by microwave assisted solvothermal method (Rejith & Krishnan 2013).

Thus, the aim of the present study is to prepare Cu-based thin film via facile approach of

AACVD and to determine the structural, electrical and optical properties of these films. The feasibility of AACVD method to synthesize binary film and the doping effect of Zn and Al to the electrical properties of Cu-based thin film is investigated.

## II. MATERIALS AND METHODS

Cu-based thin films were deposited from sol-gel solution on the borosilicate glass substrate by AACVD. Borosilicate glass substrates (Borofloat® 33, Schott) were cleaned by standard cleaning procedure of washing with soap; ultrasonic cleaning in acetone and isopropanol each for 15 min; rinsing with deionized water; and drying with  $\text{N}_2$  gas flow.

Sol-gel solution was prepared by stirring of metal precursors in solvent of absolute ethanol (99.8%, Normapur AR) for an hour and promptly proceeding to deposition. For single component of metal, metal precursor of copper (I) acetate (97%, Sigma Aldrich), zinc acetate (99.99%, Sigma Aldrich) and aluminium acetate (basic, Sigma Aldrich) were prepared separately whereas for binary component of ZnO/ $\text{Cu}_2\text{O}$  and  $\text{CuAlO}_2$ , the metal precursors were mixed together. A few drops of diethanolamine ( $\geq 98.0$  %, Sigma Aldrich) were added to the mixture to enhance the solubility of metal precursors in the solvent.

The AACVD was carried out in  $\text{N}_2$  gas flow with distance between nozzle and borosilicate glass substrate is 10 mm. The thickness of the films was varied by varying the deposition time

of 15, 30 and 60 min. Structural, optical and electrical properties of Cu-based thin film by AACVD were determined by X-ray diffraction, UV-Vis and 4-point probe, respectively.

### III. RESULTS AND DISCUSSIONS

Single metal oxide thin film of CuO and ZnO; and binary metal oxide of ZnO/Cu<sub>2</sub>O and CuAlO<sub>2</sub> thin films were successfully fabricated by AACVD. Figure 1 shows the XRD pattern for the CuO, ZnO/Cu<sub>2</sub>O and CuAlO<sub>2</sub> thin films prepared by AACVD at 400°C. XRD analysis indicated the films were crystalline with different copper phase of Cu<sub>2</sub>O, CuO and Cu with highest peak was Cu<sub>2</sub>O phase for all samples. The appearance of ZnO and CuAlO<sub>2</sub> peaks indicated that the binary metal oxide of ZnO/Cu<sub>2</sub>O and CuAlO<sub>2</sub> thin films was successfully prepared by AACVD.

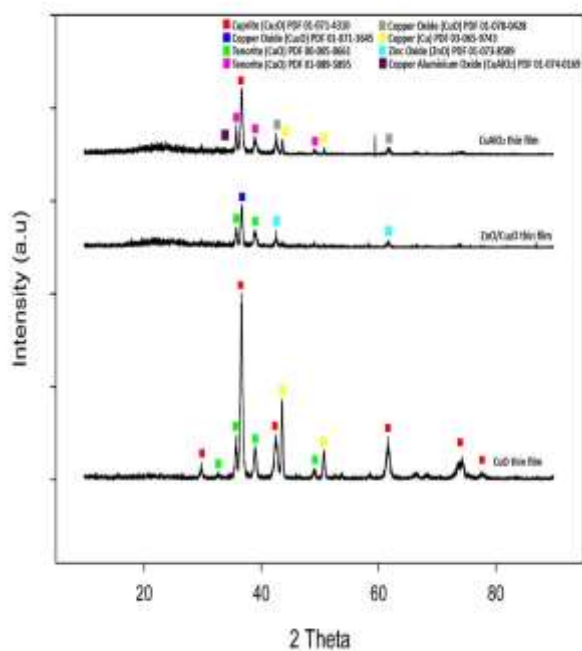


Figure 1. XRD Spectra for Cu-based thin film by AACVD.

Figure 2 shows the optical transmittance for Cu<sub>2</sub>O, ZnO, ZnO/Cu<sub>2</sub>O and CuAlO<sub>2</sub> thin films. ZnO thin film showed high optical transmittance of 100 % (550 nm) whereas Cu<sub>2</sub>O thin film showed much lower optical transmittance of 28% (550 nm). The optical transmittance was drastically reduced to 0% transparency for both ZnO/Cu<sub>2</sub>O and CuAlO<sub>2</sub> thin films. The low transparency of Cu<sub>2</sub>O, ZnO/Cu<sub>2</sub>O and CuAlO<sub>2</sub> is due to the thicker film as the deposition time increased to 1 hour, however, for film deposited at lower deposition time, the  $R_s$  is too high ( $> 10^6 \Omega/\text{sq}$ ). In Figure 3, the band gap was determined using *Tauc* plot where the band gap of Cu<sub>2</sub>O and ZnO thin film was estimated at 3.6 eV and 4.11 eV, respectively.

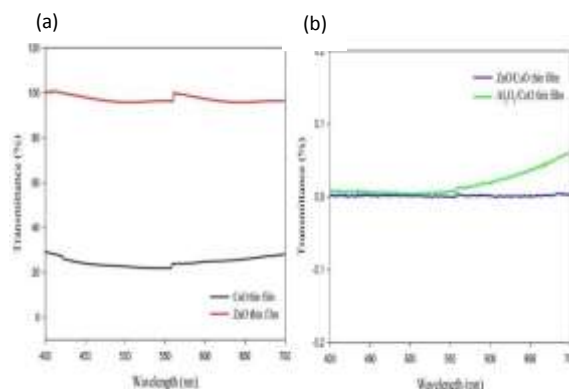


Figure 2. Transmission spectra for (a) single metal oxide of Cu<sub>2</sub>O and ZnO; and (b) binary metal oxide of ZnO/Cu<sub>2</sub>O and CuAlO<sub>2</sub> thin films.

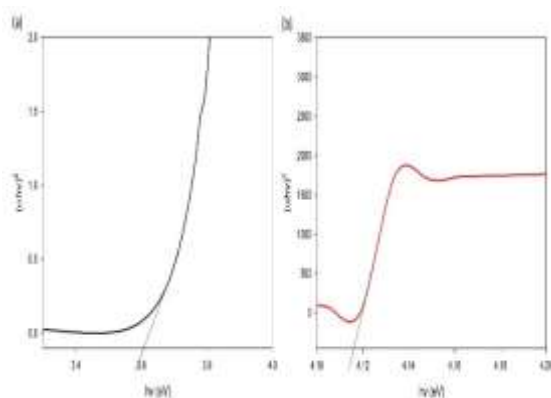


Figure 3. Tauc plot of band gap determination for (a)  $\text{Cu}_2\text{O}$  and (b)  $\text{ZnO}$  thin films.

Electrical properties of  $\text{Cu}_2\text{O}$ ,  $\text{ZnO}/\text{Cu}_2\text{O}$  and  $\text{CuAlO}_2$  thin films were summarized in Table 1. The  $R_s$  and thickness ( $t$ ) of the films was obtained by 4-point probe and surface profilometer, respectively. Resistivity ( $\rho$ ) and conductivity ( $\sigma$ ) was determined using the following formula:  $\rho = R_s \cdot t$  and  $\sigma = 1/\rho$ . The best electrical performance of  $R_s = 102.8 \text{ } \Omega/\text{sq}$  was obtained by single metal oxide of  $\text{Cu}_2\text{O}$  thin film comparable to benchmark TCF performance of ( $\sim 100 \text{ } \Omega/\text{sq}$ ) for other applications such as flat display, however, it has yet to achieve the benchmark of TCF ( $\sim 10 \text{ } \Omega/\text{sq}$ ) for front window of solar cell applications. The binary metal oxide of  $\text{ZnO}/\text{Cu}_2\text{O}$  and  $\text{CuAlO}_2$  thin films have lower electrical performance compared to single  $\text{Cu}_2\text{O}$  thin film.  $\text{Cu}_2\text{O}$  and  $\text{CuAlO}_2$  thin film synthesized by AACVD showed lower electrical performance compared to thin films synthesized by other methods in previous studies (Alkoy & Kelly 2005; Tonooka et al., 2002).

Table 1. Electrical properties of Cu-based thin film

Thin film type	$R_s$ ( $\Omega/\text{sq}$ )	$T$ ( $\mu\text{m}$ )	$\rho$ ( $\Omega.\text{cm}$ )	$\sigma$ (S/m)
$\text{Cu}_2\text{O}$	102.8	1.441	$1.481 \times 10^{-1}$	6.752
$\text{ZnO}/\text{Cu}_2\text{O}$	$5.31 \times 10^6$	1.027	$1.573 \times 10^{-4}$	$6.336 \times 10^{-5}$
$\text{CuAlO}_2$	$16.00 \times 10^6$	1.287	$2.060 \times 10^{-4}$	$4.854 \times 10^{-5}$

#### IV. SUMMARY

$\text{Cu}$ -based thin films with metal doping of Al and Zn were successfully fabricated by AACVD and properties of structural, electrical and optical for these films were investigated. XRD analysis showed three different phases of  $\text{Cu}_2\text{O}$ ,  $\text{CuO}$  and  $\text{Cu}$  were observed for single  $\text{Cu}$  thin film whereas peaks attributed to  $\text{ZnO}/\text{Cu}_2\text{O}$  and  $\text{CuAlO}_2$  were obtained for binary  $\text{Cu}$  thin film with doping of Zn and Al indicating the feasibility of AACVD to synthesize the binary film. The best electrical performance was achieved by single  $\text{Cu}_2\text{O}$  thin film with  $R_s = 102.8 \text{ } \Omega/\text{sq}$ , however, it was obtained at low  $T$  of 28%. Thus, due to low  $T$  of  $\text{Cu}_2\text{O}$  thin film, it is not suitable to be applied as TCF. In addition, the doping of Al and Zn by AACVD does not improve the electrical and optical properties of the  $\text{Cu}$ -based thin films. To improve the electrical and optical properties of  $\text{Cu}$ -based thin films by AACVD, modification to the AACVD parameters, preparation of sol-gel solution and annealing temperature is recommended.

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